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Multi-phase structured hydrogenated amorphous silicon carbon nitride thin films grown by plasma enhanced chemical vapour deposition

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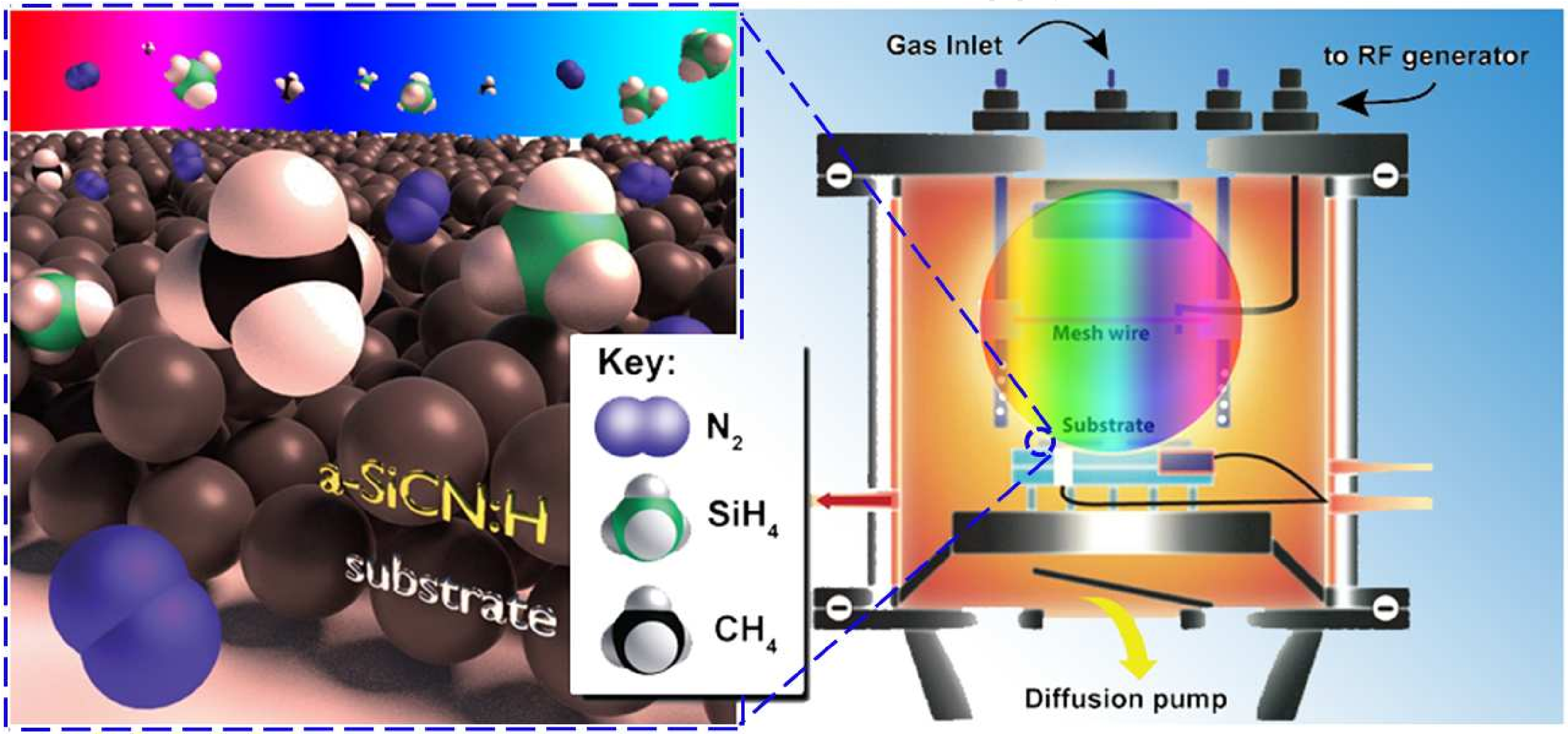
Graphical Abstract



Si (100) and glass substrates deposition with N_2 and H_2 gas molecules as precursors in PECVD chamber to form SiCN:H thin film